

| 장비번호 | 장비명 | 공정ID |
|----------|--|-----------|
| SPRCE001 | Mirror Projection Mask Aligner | SPRCOP001 |
| SPRCE002 | High resolution Raman spectrometer system | SPRCOP002 |
| SPRCE003 | FIB(Focused Ion Beam) | SPRCOP003 |
| SPRCE004 | Mask Aligner | SPRCOP004 |
| SPRCE007 | Rapid Thermal Annealing - Bosung | SPRCOP007 |
| SPRCE008 | Rapid Thermal Annealing I | SPRCOP008 |
| SPRCE009 | Rapid Thermal Annealing II | SPRCOP009 |
| SPRCE010 | CMP(Chemical-mechanical polishing) | SPRCOP010 |
| SPRCE013 | Alpha-Step (Step Height Measurement) | SPRCOP013 |
| SPRCE014 | Laser microscope | SPRCOP014 |
| SPRCE015 | Maskless photolithography system | SPRCOP015 |
| SPRCE016 | 4-Point Probe System | SPRCOP016 |
| SPRCE020 | Deep etcher | SPRCOP020 |
| SPRCE021 | Elipsometer | SPRCOP021 |
| SPRCE023 | Wire bonder | SPRCOP023 |
| SPRCE024 | Wirebonder | SPRCOP024 |
| SPRCE025 | Atomic Force Microscope (AFM) | SPRCOP025 |
| SPRCE026 | Atomic Layer Deposition | SPRCOP026 |
| SPRCE027 | Wafer Scriber | SPRCOP027 |
| SPRCE028 | Wafer track | SPRCOP028 |
| SPRCE029 | Wet Station(acid) | SPRCOP029 |
| SPRCE030 | Wet Station(organic) | SPRCOP030 |
| SPRCE032 | Inductively Coupled Plasma/Reactive Ion Etching(Cl)-Tainics | SPRCOP032 |
| SPRCE033 | Inductively Coupled Plasma/Reactive Ion Etching(Cl)-Plasma Therm | SPRCOP033 |
| SPRCE034 | Inductively Coupled Plasma/Reactive Ion Etching(F)-Sorona | SPRCOP034 |
| SPRCE035 | Chemical Mechanical Planarization | SPRCOP035 |
| SPRCE036 | Metal Organic Chemical Vapor Deposition I | SPRCOP036 |
| SPRCE037 | Ion sputter (SEM) | SPRCOP037 |
| SPRCE038 | Integrating spheres for UV/VIS spectrometer | SPRCOP038 |
| SPRCE039 | E-beam evaporator (ULVAC) | SPRCOP039 |
| SPRCE040 | E-beam Evaporator | SPRCOP040 |
| SPRCE041 | E-beam Evaporator - KVT | SPRCOP041 |
| SPRCE042 | Field Emission Scanning Electron Microscope | SPRCOP042 |
| SPRCE043 | Field Emission Scanning Electron Microscope - Hitachi | SPRCOP043 |
| SPRCE045 | Plasma Enhanced Chemical Vapor Deposition II (BMR) | SPRCOP045 |
| SPRCE046 | Plasma Enhanced Chemical Vapor Deposition I (Oxford) | SPRCOP046 |
| SPRCE048 | Direct Current Sputtering System | SPRCOP048 |
| SPRCE050 | Spin Coater | SPRCOP050 |
| SPRCE052 | Radio Frequency Sputtering System Sputtering System II | SPRCOP052 |

| 공정명 | 버전 | 의뢰기본. |
|--|----|--------|
| Mirror Projection Mask Aligner | 1 | 0 |
| High resolution Raman spectrometer system | 1 | 0 |
| FIB(Focused Ion Beam) | 1 | 0 |
| Mask Aligner | 1 | 0 |
| Rapid Thermal Annealing - Bosung | 1 | 0 |
| Rapid Thermal Annealing I | 1 | 0 |
| Rapid Thermal Annealing II | 1 | 0 |
| CMP(Chemical-mechanical polishing) | 1 | 0 |
| Alpha-Step (Step Height Measurement) | 1 | 0 |
| Laser microscope | 1 | 0 |
| Maskless photolithography system | 1 | 0 |
| 4-Point Probe System | 1 | 0 |
| Deep etcher | 1 | 0 |
| Elipsometer | 1 | 0 |
| Wire bonder | 1 | 0 |
| Wirebonder | 1 | 0 |
| Atomic Force Microscope (AFM) | 1 | 0 |
| Atomic Layer Deposition | 1 | 0 |
| Wafer Scriber | 1 | 20,000 |
| Wafer track | 1 | 0 |
| Wet Station(acid) | 1 | 0 |
| Wet Station(organic) | 1 | 0 |
| Inductively Coupled Plasma/Reactive Ion Etching(Cl)-Tainics | 1 | 0 |
| Inductively Coupled Plasma/Reactive Ion Etching(Cl)-Plasma Therm | 1 | 0 |
| Inductively Coupled Plasma/Reactive Ion Etching(F)-Sorona | 1 | 0 |
| Chemical Mechanical Planarization | 1 | 0 |
| Metal Organic Chemical Vapor Deposition I | 1 | 0 |
| Ion sputter (SEM) | 1 | 0 |
| Integrating spheres for UV/VIS spectrometer | 1 | 0 |
| E-beam evaporator (ULVAC) | 1 | 0 |
| E-beam Evaporator | 1 | 0 |
| E-beam Evaporator - KVT | 1 | 0 |
| Field Emission Scanning Electron Microscope | 1 | 0 |
| Field Emission Scanning Electron Microscope - Hitachi | 1 | 0 |
| Plasma Enhanced Chemical Vapor Deposition II (BMR) | 1 | 0 |
| Plasma Enhanced Chemical Vapor Deposition I (Oxford) | 1 | 0 |
| Direct Current Sputtering System | 1 | 0 |
| Spin Coater | 1 | 0 |
| Radio Frequency Sputtering System Sputtering System II | 1 | 0 |

| 인건비 | 의뢰수가 | 1의뢰단위 | 1의뢰수가 | 의뢰단위 | 의뢰수가 | 의뢰단위 | 직접사용 | 직접사용수 |
|-----|---------|--------|--------|------|------|------|---------|-------|
| 0 | 36,000 | EA | 0 | | 0 | | 24,000 | 0 |
| 0 | 24,000 | EA | 0 | | 0 | | 24,000 | 0 |
| 0 | 200,000 | HOUR | 0 | | 0 | | 160,000 | 0 |
| 0 | 36,000 | EA | 0 | | 0 | | 24,000 | 0 |
| 0 | 48,000 | COUNT | 0 | | 0 | | 32,000 | 0 |
| 0 | 48,000 | COUNT | 0 | | 0 | | 32,000 | 0 |
| 0 | 48,000 | COUNT | 0 | | 0 | | 32,000 | 0 |
| 0 | 112,000 | EA | 0 | | 0 | | 64,000 | 0 |
| 0 | 24,000 | HOUR | 0 | | 0 | | 24,000 | 0 |
| 0 | 24,000 | HOUR | 0 | | 0 | | 16,000 | 0 |
| 0 | 4,000 | MINUTE | 0 | | 0 | | 3,200 | 0 |
| 0 | 24,000 | HOUR | 0 | | 0 | | 0 | 0 |
| 0 | 160,000 | COUNT | 0 | | 0 | | 120,000 | 0 |
| 0 | 24,000 | COUNT | 0 | | 0 | | 24,000 | 0 |
| 0 | 36,000 | HOUR | 18,000 | HOUR | 0 | | 24,000 | 0 |
| 0 | 36,000 | HOUR | 18,000 | HOUR | 0 | | 24,000 | 0 |
| 0 | 70,000 | HOUR | 85,000 | HOUR | 0 | | 35,000 | 0 |
| 0 | 80,000 | COUNT | 0 | | 0 | | 64,000 | 0 |
| 0 | 24,000 | HOUR | 0 | | 0 | | 2,000 | 0 |
| 0 | 24,000 | EA | 0 | | 0 | | 16,000 | 0 |
| 0 | 96,000 | COUNT | 0 | | 0 | | 72,000 | 0 |
| 0 | 96,000 | COUNT | 0 | | 0 | | 72,000 | 0 |
| 0 | 80,000 | COUNT | 0 | | 0 | | 56,000 | 0 |
| 0 | 80,000 | COUNT | 0 | | 0 | | 56,000 | 0 |
| 0 | 80,000 | COUNT | 0 | | 0 | | 51,000 | 0 |
| 0 | 112,000 | EA | 0 | | 0 | | 64,000 | 0 |
| 0 | 320,000 | COUNT | 0 | | 0 | | 240,000 | 0 |
| 0 | 10,000 | COUNT | 0 | | 0 | | 0 | 0 |
| 0 | 35,000 | HOUR | 0 | | 0 | | 25,000 | 0 |
| 0 | 120,000 | COUNT | 0 | | 0 | | 80,000 | 0 |
| 0 | 120,000 | COUNT | 0 | | 0 | | 80,000 | 0 |
| 0 | 120,000 | COUNT | 0 | | 0 | | 80,000 | 0 |
| 0 | 54,000 | HOUR | 24,000 | EA | 0 | | 37,000 | 0 |
| 0 | 54,000 | HOUR | 0 | | 0 | | 37,000 | 0 |
| 0 | 80,000 | COUNT | 0 | | 0 | | 64,000 | 0 |
| 0 | 80,000 | COUNT | 0 | | 0 | | 64,000 | 0 |
| 0 | 64,000 | EA | 0 | | 0 | | 48,000 | 0 |
| 0 | 24,000 | EA | 0 | | 0 | | 16,000 | 0 |
| 0 | 0 | EA | 0 | | 0 | | 48,000 | 0 |

직접사용단 직접사용수 직접사용단 직접사용수 직접사용단 적용시작일

| | | | |
|--------|-------------|---|-----------------------|
| EA | 0 | 0 | 2025-07-01 09:00:00.0 |
| EA | 0 | 0 | 2025-07-01 09:00:00.0 |
| HOUR | 0 | 0 | 2025-07-01 09:00:00.0 |
| EA | 0 | 0 | 2025-07-01 09:00:00.0 |
| COUNT | 0 | 0 | 2025-07-01 09:00:00.0 |
| COUNT | 0 | 0 | 2025-07-01 09:00:00.0 |
| COUNT | 0 | 0 | 2025-07-01 09:00:00.0 |
| EA | 0 | 0 | 2025-07-01 09:00:00.0 |
| HOUR | 0 | 0 | 2025-07-01 09:00:00.0 |
| HOUR | 0 | 0 | 2025-07-01 09:00:00.0 |
| MINUTE | 0 | 0 | 2025-07-01 09:00:00.0 |
| HOUR | 0 | 0 | 2025-07-01 09:00:00.0 |
| COUNT | 0 | 0 | 2025-07-01 09:00:00.0 |
| COUNT | 0 | 0 | 2025-07-01 09:00:00.0 |
| HOUR | 12,000 HOUR | 0 | 2025-07-01 09:00:00.0 |
| HOUR | 12,000 HOUR | 0 | 2025-07-01 09:00:00.0 |
| HOUR | 0 | 0 | 2025-07-01 09:00:00.0 |
| COUNT | 0 | 0 | 2025-07-01 09:00:00.0 |
| EA | 0 | 0 | 2025-07-01 09:00:00.0 |
| EA | 0 | 0 | 2025-07-01 09:00:00.0 |
| COUNT | 0 | 0 | 2025-07-01 09:00:00.0 |
| COUNT | 0 | 0 | 2025-07-01 09:00:00.0 |
| COUNT | 0 | 0 | 2025-07-01 09:00:00.0 |
| COUNT | 0 | 0 | 2025-07-01 09:00:00.0 |
| COUNT | 0 | 0 | 2025-07-01 09:00:00.0 |
| COUNT | 0 | 0 | 2025-07-01 09:00:00.0 |
| EA | 0 | 0 | 2025-07-01 09:00:00.0 |
| COUNT | 0 | 0 | 2025-07-01 09:00:00.0 |
| HOUR | 0 | 0 | 2025-07-01 09:00:00.0 |
| HOUR | 0 | 0 | 2025-07-01 09:00:00.0 |
| COUNT | 0 | 0 | 2025-07-01 09:00:00.0 |
| COUNT | 0 | 0 | 2025-07-01 09:00:00.0 |
| COUNT | 0 | 0 | 2025-07-01 09:00:00.0 |
| HOUR | 16,000 EA | 0 | 2025-07-01 09:00:00.0 |
| HOUR | 0 | 0 | 2025-07-01 09:00:00.0 |
| COUNT | 0 | 0 | 2025-07-01 09:00:00.0 |
| COUNT | 0 | 0 | 2025-07-01 09:00:00.0 |
| EA | 0 | 0 | 2025-07-01 09:00:00.0 |
| EA | 0 | 0 | 2025-07-01 09:00:00.0 |
| EA | 0 | 0 | 2025-07-01 09:00:00.0 |

